

| Ref # | Hits | Search Query   | DBs  | Default Operator | Plurals | Time Stamp       |
|-------|------|--|--|------------------|---------|------------------|
| L1    | 717  | CMOS same implant\$4 same anneal\$3  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:39 |
| L2    | 229  | CMOS same implant\$4 same anneal\$3 same polysilicon   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 08:53 |
| L3    | 18   | 2 and silicidation   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 08:21 |
| L4    | 3    | CMOS same implant\$4 same anneal\$3 same (polysilicon with resistor)   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 08:54 |
| L5    | 39   | CMOS and implant\$4 and anneal\$3 and (polysilicon with resistor) and silicidation   | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:39 |
| L9    | 96   | CMOS same implant\$4 same (anneal\$3 and heat\$4)  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:39 |
| L10   | 53   | CMOS and (implant\$4 or dop\$4) and (anneal\$3 or heat\$4) and (polysilicon with resistor) and silicidation  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:41 |
| L11   | 933  | CMOS and (implant\$4 or dop\$4) and (anneal\$3 or heat\$4) and (polysilicon or conductive) and silicidation  | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:40 |
| L12   | 952  | CMOS and (implant\$4 or dop\$4) and (anneal\$3 or heat\$4) and (polysilicon or titanium or cobalt or nickel) and silicidation                            | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:41 |
| L13   | 76   | (titanium or ti or cobalt or Nickel) and (implant\$4 or dop\$4) and (anneal\$3 or heat\$4) and (polysilicon with resistor) and silicidation              | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:42 |
| L14   | 1077 | (titanium or ti or cobalt or Nickel) and (implant\$4 or dop\$4) and (anneal\$3 or heat\$4) and polysilicon and (resistor or resistance) and silicidation | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/05/03 09:43 |

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|-----|-----|-------------|--|----|-----|------------------|
| L15 | 608 | 14 and CMOS | USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/05/03 09:43 |
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